SUPERCRITICAL CPD MEMS DRYER FOR 4" (100mm) WAFERS

Autosamdri®-815B, Series B

tousimis





- The Supercritical **Autosamdri**®-**815B**, **Series B** System was developed by Dr. A.J. Tousimis and our team of long-standing associates within the tousimis® SAMDRI design group.
- Smooth operation and precise control are the Supercritical **Autosamdri***-815B's trademark; wafer holders and inserts are provided that allow anti-stiction processing up to 5 pieces of either 4", 3", 2" wafers or 10mm square die per process run!

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SUPERCRITICAL Autosamdri®-815B, Series B

Catalog# 8780C (Process Various Wafer Sizes up to 4in - 100mm)

FEATURES

- Microprocessor controller allows for complete automatic processing.*
- All internal surfaces are inert to CO2 and ultrapure alcohols.*
- Repeatable operating parameters insuring reproducibility of results.*
- Integrated temperature controls.*
- Internal rupture disc built in for safety. *
- Processes up to 5 x 4" (100mm) diam. wafers per run; comes with additional HF compatible wafer holders to process 5 x 3" (75mm), 5 x 2" (50mm) diameter wafers or 5 x 10mm square die (tousimis® HF compatible Wafer Holders* can be used to transport and process your wafers and die from HF).
- All electronic components meet CE, UL and/or U.S. Military Specifications.
- Static pressure control module pre-set for automatic safe pressure stability.
- 0.08µm internal filtration system delivers clean filtered LCO₂ to process chamber.
- Under-lit chamber with viewing window facilitates operator chamber status viewing.
- An efficient adiabatic cooling system*, capable of cooling the chamber from ambient room temperature to near 0°C, in less than 3 minutes and maintains temperature automatically during both FILL and PURGE modes.*
- LED's instantly indicate process mode at a glance.*
- · Clean room static-free compatible design.
- For added safety and convenience, the U.S. Patented SOTER™ condenser* quietly captures exhaust and alcohols.
- Unique chamber inserts* allow variance of chamber I.D. This maximizes efficiency in LCO₂ consumption and processing time.
- On-site Start-up and User(s) Training by a qualified tousimis® technician included.1

SPECIFICATIONS

- Cabinet: 14.25" (36.2cm) Width x 11.75" (29.8cm) Height x 25" (63.5cm) Length
- System Set-Up Area Required: 42" (107cm) Width x 30" (76cm) Depth
- Chamber size: 4.50" I.D. x 1.25" depth Chamber volume: 326 ml
- Temperature gauge range: -30°C to 60°C, Pressure gauge range: 0 to 2,000psi
- 120V/50-60Hz (Other voltage units also available. Please Inquire)
- LCO2 flow is controlled through Micro Metering Valves with Vernier handles for easily controlled flow rates.*

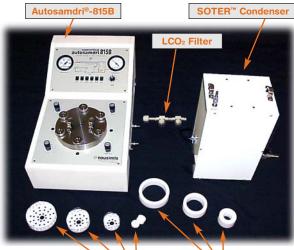
STANDARD ACCESSORIES

- LCO₂ High Pressure braided stainless steel inert Teflon® lined hose. 10ft (~ 3m) long for clean room operation (at a nominal charge, other lengths available upon request).
- Double T-Filter Assembly (#8785) pre-installed onto the chamber LCO₂ supply high-pressure hose. Flows LCO₂ twice thru 0.5 µm filters with 99.5% particulate retention prior to LCO₂ entering Autosamdri®-815B.
- New SOTER[™] Condenser* connects to exhaust hose. Captures all alcohol and deadens exhaust noise.*
- Static free Exhaust Tubing for all exhaust outlets.
- Internal stainless and nickel scintered filtration systems incorporated to protect lines, wafers, and valves down to 0.4µm.
- Spare Chamber O-ring (3), Chamber Lamp (1), and 5A Slo-Blow Fuses (2).
- 3 Chamber Inserts.* Enables original chamber ID reduction down to smaller chamber ID sizes for a range including: 4", 3", 2", and 1.25"!
- 4" (100mm), 3" (75mm), 2" (50mm) diameter Wafer Holders and 10mm square Die Holder included. Holders are HF compatible and can hold up to 5 wafers or die each.
- Free lifetime technical support consultation by our scientific staff.
- 2 year warranty on all parts and labor.



^{*} Most Autosamdri* feature U.S. patents (# 6,493,964, #6,678,968) or patents pending.

Note: Actual delivered model or accessories may vary slightly, as advancements are being constantly applied.



HF Compatible Wafer Holders

